## Atomic scale STM/STS analysis on transition metal

## dichalcogenide heterostructures

<u>R. Sakurada<sup>1</sup></u>, S. Yoshida<sup>1</sup>, A. Taninaka<sup>1</sup>, Y. Kobayashi<sup>2</sup>, H. Mogi<sup>1</sup>, T. Kouyama<sup>1</sup>, Y. Miyata<sup>2</sup>, O. Takeuchi<sup>1</sup> and H. Shigekawa<sup>1</sup>

<sup>1</sup>Institute of Applied Physics, University of Tsukuba, Tsukuba, Ibaraki 305-8573, Japan. <sup>2</sup> Department of Physics, Tokyo Metropolitan University, Hachioji, Tokyo 192-0397, Japan.

Transition-metal dichalcogenide layered materials, consisting of a transition-metal atomic layer sandwiched by two chalcogen atomic layers, have been attracting considerable attention because of their desirable physical properties for semiconductor devices, and a wide variety of pn junctions, which are essential building blocks for electronic and optoelectronic devices, have been realized using these atomically thin structures. Engineering the electronic/optical properties of semiconductors by using such heterojunctions has been a central concept in semiconductor science and technology. Here, we report the first scanning tunneling microscopy/spectroscopy (STM/STS) study on the electronic structures of a monolayer WS<sub>2</sub>/Mo<sub>1-x</sub>W<sub>x</sub>S<sub>2</sub> heterojunction that provides a tunable band alignment<sup>1</sup>. Fig.1 shows a typical STM image of  $Mo_{1-x}W_xS_2$  monolayer alloy with a triangular shape. Smaller bright triangular area inside monolayer is corresponds to Mo<sub>1-x</sub>W<sub>x</sub>S<sub>2</sub> which is surrounded by outer WS<sub>2</sub>. Fig.2 shows the empty state STM image (Vs = +1.35V) around WS<sub>2</sub>/Mo<sub>1-x</sub>W<sub>x</sub>S<sub>2</sub> heterojunction interface. Mo<sub>1-x</sub>W<sub>x</sub>S<sub>2</sub> side appears brighter due to lower energy of conduction band minimum ( $E_{CBM}$ ) of MoS2 compared to that of WS<sub>2</sub>. Fig. 3 shows a map of dI/dV calculated from the spatially resolved STS measured across the interface. The upper and lower edges of the band gap region, corresponding respectively to  $E_{CBM}$  and  $E_{VBM}$ , continuously shifted as a function of the distance across the interface, whose position was determined from the STM image and is indicated by the dashed line. The result clearly demonstrates that a type-II staggered gap heterojunction with a nanoscale built-in potential distribution was formed at the interface



Fig a. STM image of a  $WS_2/Mo_{1-x}W_xS_2$  monolayer on graphite b. Magnification of the part of the heterojunction interface c. dI/dV profile across the heterojunction interface <sup>1.</sup> S.Yoshida, et al., Sci. Rep. 5, 14808 (2015)